

[ABSTRACT]

The present invention relates to a method for manufacturing polycrystalline silicon fragments including: a step of producing a polycrystalline silicon rod by the Siemens method; a step of crushing the polycrystalline silicon rod to obtain polycrystalline silicon fragments; and a step of cleaning by etching the polycrystalline silicon fragments in a cleaning tank. In the cleaning step, small pieces of the polycrystalline silicon having controlled shapes and sizes are present in the cleaning tank and the weight change of the small pieces of the polycrystalline silicon before and after the etching step is measured to thereby manage the cleaning step. The present invention also relates to a method for managing the surface metal concentration of the polycrystalline silicon fragments.

[No Figure]